# Study on Chemical Vapor Deposition of Ultra High Temperature Ceramics Based on Prediction of Thermodynamic Equilibrium Phases

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# 1. Introduction

Ultra high temperature ceramics (UHTCs) such as  $ZrB_2$ ,  $HfB_2$ , ZrC, HfC, and TaC have extremely high melting points above 3000K [1,2]. They have excellent resistance to chemical attack, corrosion, and mechanical/thermal stress. Also, some UHTCs show good neutron characteristics. For example, ZrC has low neutron absorption cross section while  $HfB_2$  has high neutron absorption cross section. Therefore, they can be used as constituent coating layer of TRISO fuel particles and neutron shielding materials [3]. In this study, we calculated thermodynamic equilibrium phases in  $HfCl_4$ - $C_3H_6$ - $H_2$  system and derived optimal deposition conditions. Based on the calculation we tried to deposit a single HfC phase at a low temperature of  $1200^{\circ}C$ .

#### 2. Methods and Results

# 2.1 Thermal Equilibrium Calculation

We used the HSC Chemistry 9.0 software to calculate thermodynamic equilibrium phases in the  $HfCl_4$ - $C_3H_6$ - $H_2$  system. Following equations shows the reactions in the  $HfCl_4$ - $C_3H_6$ - $H_2$  system.

$$\begin{split} HfCI_4(g) + H_2(g) + 1/3C_3H_6(g) &= HfC(s) + 4HCI(g); \\ 1/3C_3H_6(g) \to C(s) + H_2(g) \\ HfCI_4(g) + 2H_2(g) \to Hf(s) + 4HCI(g) \\ C(s) + Hf(s) \to HfC(s) \end{split}$$

Fig. 1 shows the equilibrium phases depending on the temperature at 1200°C, 6.7 kPa. HfC begins to form at about 500°C and HfCl<sub>4</sub>:C<sub>3</sub>H<sub>6</sub>:H<sub>2</sub> = 3:0.32:100. A near-single phase HfC forms above 1200°C, as shown in Fig. 1(a). Fig. 1(b) shows the C/HfC ratio in HfC-1 and HfC-2 deposition conditions. The amount of excess carbon decreases as H<sub>2</sub> increases.



Fig. 1. (a) Equilibrium phases and (b) C/HfC ratio in the HfCl4-C<sub>3</sub>H<sub>6</sub>-H<sub>2</sub> system [4].

#### 2.2 Chemical Vapor Deposition of HfC

Deposition was performed at 1200°C and 6.7 kPa based on thermodynamic equilibrium calculation results. Table I shows the chemical vapor deposition conditions.

Table I: Deposition Conditions of HfC

Sample	Flow rate (sccm)			
designation	C <sub>3</sub> H <sub>6</sub>	H <sub>2</sub>	Ar	HfCl <sub>4</sub>
HfC-1	10	3200	0	91
HfC-2	10	800	0	91

Fig. 2 shows the XRD results of HfC deposited at 1200°C. At the high ratio of  $H_2/(HfCl_4+C_3H_6)$ , a nearly single HfC phase was deposited, but a small amount of excess carbon was co-deposited in HfC at the lower ratio of  $H_2/(HfCl_4+C_3H_6)$ .



Fig. 2. X-ray diffraction peaks of hafnium carbides.

Fig. 3 shows the cross-sectional microstructure of the HfC coating layers of HfC-1 and HfC-2. HfC deposited in the HfC-1 condition contains many pores and the grain size is small. Also, HfC nanorods with a diameter of several hundred nanometers were grown. On the other hand, in the HfC-2 condition, HfC has a dense structure without pores, and the grain is coarse.



Fig. 3. Microstructures of HfC coatings: (a) HfC-1 and (b) HfC-2.

# 3. Conclusions

HfC was deposited at  $1200^{\circ}$ C by chemical vapor deposition from HfCl<sub>4</sub>-C<sub>3</sub>H<sub>6</sub>-H<sub>2</sub> which was derived from thermodynamic calculation. a single HfC phase without excess carbon, was deposited at a high ratio of H<sub>2</sub>/(HfCl<sub>4</sub>+C<sub>3</sub>H<sub>6</sub>). However, a porous HfC coating layer was formed. On the other hand, dense HfC was

deposited at the low ratio of  $H_2/(HfCl_4+C_3H_6)$  although it contains a small amount of excess in the HfC coating.

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